

**Amendments to the Specification:**

Please replace the paragraph beginning at page 34, line 1, with the following amended paragraph:

Then, a silicon oxide film was formed as an interlayer insulator 810 by sputtering method. In place of the sputtering method, LPCVD method, photo CVD method, and normal pressure CVD may be utilized for the formation of the silicon oxide film. The thickness of the layer was 0.2 to 0.6 $\mu$ m, for example. After that, an opening 811 for electrode was formed using a ~~[[forth]]~~ fourth photomask (84). On the entire surface of this structure, an aluminum film having a thickness of 0.3  $\mu$ m was formed by sputtering method, and then a lead 812 and a contact 813 were formed using a photomask (85). An organic resin for ~~surface-flattering~~ surface-flattening 814, e.g. a transparent polyimide resin was then applied on the top surface, and further an opening for an electrode was again formed using a sixth photomask (86).

Please replace the paragraph beginning at page 40, line 17, with the following amended paragraph:

After forming each TFT 1209 in the form of island by the use of a third photomask (23), an organic resin 1210 for ~~surface-flattering~~ surface-flattening, e.g. a transparent polyimide resin, was applied as shown in Fig. 12(D), and an opening for electrode was again formed by the use of a photomask (24).

Please replace the paragraph beginning at page 45, line 21, with the following amended paragraph:

An organic resin film 1412 for ~~surface-flattering~~ surface-flattening, e.g. a transparent polyimide resin film was formed, and an opening for an electrode was formed using photomask (35).

Please replace the paragraph bridging pages 52 and 53 with the following amended paragraph:

An organic resin for ~~surface-flattering~~ surface-flattening 685, e.g. a transparent polyimide resin was then applied on the top surface, and further an opening for electrode was again formed using a ninth photomask 686.

Please replace the paragraph beginning at page 60, line 6, with the following amended paragraph:

An organic resin film 624 for ~~surface-flattering~~ surface-flattening, e.g. a transparent polyimide resin film was formed, and electrode an opening for an electrode was provided using a photomask (46).